

ABSTRACT

A process is defined for depositing a silica coating upon a heated glass substrate. The process includes providing a heated glass substrate having a surface upon which the coating is to be deposited. A precursor mixture comprising a silane, an oxygen source, a radical scavenger, a phosphorous (V) compound and an inert carrier gas is directed toward and along the surface to be coated. The mixture is reacted at or near the surface to form a silica coating on the surface of the glass substrate.